

Inventor: H. Daniel Dulman et al.

Title: Methods Of Forming Aligned Structures With Radiation-Sensitive Material

Assignee: Micron Technology, Inc.

Serial No.: Filed Herewith

Filing Date: Filed Herewith

**INFORMATION DISCLOSURE STATEMENT**


**PURSUANT TO 37 C.F.R. §§1.56, 1.97 AND 1.98**

In compliance with 37 C.F.R. §§1.56, 1.97 and 1.98, your attention is directed to the references listed on the attached Form PTO-1449.

The listed references were cited by, or submitted to, the Office in the parent, co-pending application of the above-identified application. The above-identified application is a divisional of co-pending application Serial No. 10/226,005, filed August 21, 2002. Such prior disclosure is sufficient for the above-identified application as far as copies of the references are concerned. 37 C.F.R. §1.98(d) and MPEP §609(2). No admission is made regarding whether all the submitted references are prior art.

Citation of these references is respectfully requested.

Respectfully submitted,

Dated: 3/24/04 Attorney:   
David G. Latwesen, Ph.D.  
Reg. No. 38,533  
WELLS, ST. JOHN P.S.

EV372453785

Form PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. M122-2514		SERIAL NO. Filed Herewith	
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)				APPLICANT H. Daniel Dulman et al.			
				FILING DATE Filed Herewith		GROUP Unknown	

U.S. PATENT DOCUMENTS							
*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
	AA	5,308,721	05/94	Garofalo et al.			
	AB						
	AC						
	AD						
	AE						
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	AG						
	AH						
	AI						
	AJ						
	AK						
	AL						

FOREIGN PATENT DOCUMENTS								
		Document Number	Date	Country	Class	Subclass	Translation	
							Yes	No
	AM							
	AN							
	AO							
	AP							
	AQ							

OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)		
	AR	Kobayashi, S. et al., "Development of Simplified Process for KrF Excimer Half-Tone Mask with Chrome-Shielding Method", 19th Annual BACUS Sympos. on Photomask Technology, Monterey, CA, 9/99, SPIE Vol. 3873 (1999), pp. 288-296.
	AS	Kobayashi, S. et al., "Development of Simplified Process for KrF Excimer Half-Tone Mask with Chrome-Shielding Method (II)", 20th Annual BACUS Sympos. on Photomask Technology, Proceedings of SPIE Vol. 4186 (2001), pp.801-809.
	AT	

EXAMINER	DATE CONSIDERED
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\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.